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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO
09/877,145	06/11/2001	Itsuko Sakai	04329.2574	1279
22852	7590 02/24/2004		EXAMINER	
FINNEGAN, HENDERSON, FARABOW, GARRETT & DUNNER			TRAN, BINH X	
LLP 1300 I STREE	T. NW		ART UNIT	PAPER NUMBER
WASHINGTON, DC 20005		1765		

DATE MAILED: 02/24/2004

Please find below and/or attached an Office communication concerning this application or proceeding.

*	Application No.	Applicant(s)	\bigcirc				
Advisory Action	09/877,145	SAKAI ET AL.	(Y)				
, avicery , telien	Examiner	Art Unit					
	Binh X Tran	1765					
The MAILING DATE of this communication appears on the cover sheet with the correspondence address							
THE REPLY FILED 09 February 2004 FAILS TO PLACE Therefore, further action by the applicant is required to a final rejection under 37 CFR 1.113 may only be either: (*condition for allowance; (2) a timely filed Notice of Appel Examination (RCE) in compliance with 37 CFR 1.114.	void abandonment of this application (i) a timely filed amendment whi	cation. A proper re ch places the appli	ply to a cation in				
PERIOD FOR RE	PLY [check either a) or b)]						
a) The period for reply expiresmonths from the mailing of							
b) The period for reply expires on: (1) the mailing date of this Advevent, however, will the statutory period for reply expire later th ONLY CHECK THIS BOX WHEN THE FIRST REPLY WAS 706.07(f).	an SIX MONTHS from the mailing date of FILED WITHIN TWO MONTHS OF THE	f the final rejection. E FINAL REJECTION.	See MPEP				
Extensions of time may be obtained under 37 CFR 1.136(a). The da have been filed is the date for purposes of determining the period of extension 37 CFR 1.17(a) is calculated from: (1) the expiration date of the shortened (b) above, if checked. Any reply received by the Office later than three more earned patent term adjustment. See 37 CFR 1.704(b).	sion and the corresponding amount of the I statutory period for reply originally set in	e fee. The appropriate ex the final Office action; or	tension fee under (2) as set forth in				
1. A Notice of Appeal was filed on Appellant's 37 CFR 1.192(a), or any extension thereof (37 CF							
2. The proposed amendment(s) will not be entered b	ecause:						
(a) they raise new issues that would require furth	er consideration and/or search ((see NOTE below);					
(b) they raise the issue of new matter (see Note b	pelow);						
(c) they are not deemed to place the application issues for appeal; and/or	in better form for appeal by mat	erially reducing or	simplifying the				
(d) they present additional claims without cancel	ing a corresponding number of	finally rejected clai	ms.				
NOTE:			•				
3. Applicant's reply has overcome the following reject	ction(s):						
4. Newly proposed or amended claim(s) would canceling the non-allowable claim(s).	be allowable if submitted in a s	eparate, timely file	d amendment				
 5. ☐ The a) ☐ affidavit, b) ☐ exhibit, or c) ☐ required place the application in condition for allow 6. ☐ The affidavit or exhibit will NOT be considered becaused by the Examiner in the final rejection. 	ance because: See Continuation	Sheet.					
7. For purposes of Appeal, the proposed amendment explanation of how the new or amended claims we			and an				
The status of the claim(s) is (or will be) as follows:		• ()					
Claim(s) allowed:							
Claim(s) objected to: 8 and 9							
Claim(s) rejected: <u>1-7 and 10-17</u> .							
Claim(s) withdrawn from consideration: 18-31.							
8. The drawing correction filed on is a) app	proved or b) disapproved by	the Examiner.					
9. Note the attached Information Disclosure Stateme	nt(s)(PTO-1449) Paper No(s).						
10. Other:							
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Continuation of 5. does NOT place the application in condition for allowance because:

The applicants disagree with the examiner's position that Nozawa teaches "to re-circulate part of the process gas exhausted from the process chamber into the process chamber". According to applicants, Nozawa's reference requires refining mechanism wherein the applicant's invention does not. The examiner acknowledges that Nozawa's reference requires refining mechanism. However, this argument is not commensurate with the scope of the claims because there is no limitation in the claims with excluding the refining mechanism.

The applicants further argue that the examiner has "failed to establish a prima facie case for obviousness because there is no motivation to combine Chao et al. and Nozawa et al". According to applicants the refining mechanism of Nozawa requires additional cost. The examiner disagrees. First as discussed above, there is no limitation in the claims which excluding the refining mechanism. Second, while refining mechanism may cost some money, but the over all operation cost will reduce comparing with using all new materials without refining or recycling.

The applicants further argue that the exhaust gas is "reintroduced (as it is) as recovering gas. As a result, gas which is introduced again into the chamber as recovered gas is made of the components DIFFERENT from the components of the newly introduced gas." This argument is not commensurate with the scope of the claims. There is no limitation in the claims indicating that the exhaust gas is reintroduced "as it is" or "the recovered gas is made of different components from the newly introduced gas".

The applicants argue, "Since Nozawa et al. teaches that the components of recovered gas and introduced gas are the same, they can be introduced into the chamber according to the same introducing condition". The examiner strongly disagrees. The examiner recognizes that the recovering gas and newly introducing gas in Nozawa's reference have the same chemical components. However, this does not mean that they both have the same introducing condition. On the contrary, Nozawa discloses a plasma process using different valve to control the condition (such as flow rate, circulation ratio, etc) for the recovering gas and newly introducing gas.

The applicants further argue that Chao's monitoring system is "used during the processing, on order to determine the etching state". According to applicants, "Chao et al. does not determine a gas flow rate". The examiner strongly disagrees. In col. 5 lines 37-42, Chao clearly states, "the process parameters for performing a specific process related to process condition such as process gas composition and flow rate...chamber wall temperature"

Binh X. Tran